

**Supplementary Table 1**

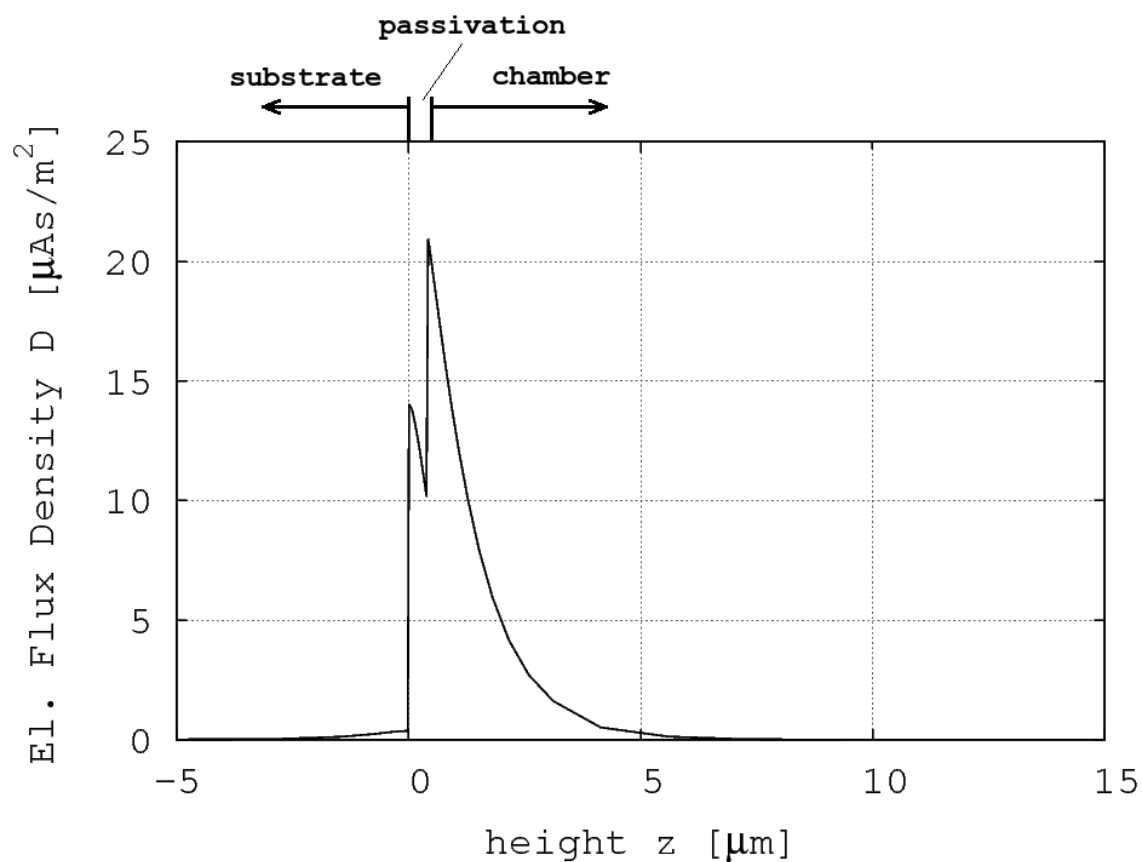
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Capacitance at 2000 Hz	Air filled chamber	DI water filled chamber	Absence of passivation, air filled chamber
<i>C<sub>experimental</sub> [pF]</i>	8.4	29.9	5.6
<i>C<sub>numerical</sub> [pF]</i>	8.1	28.6	5.8

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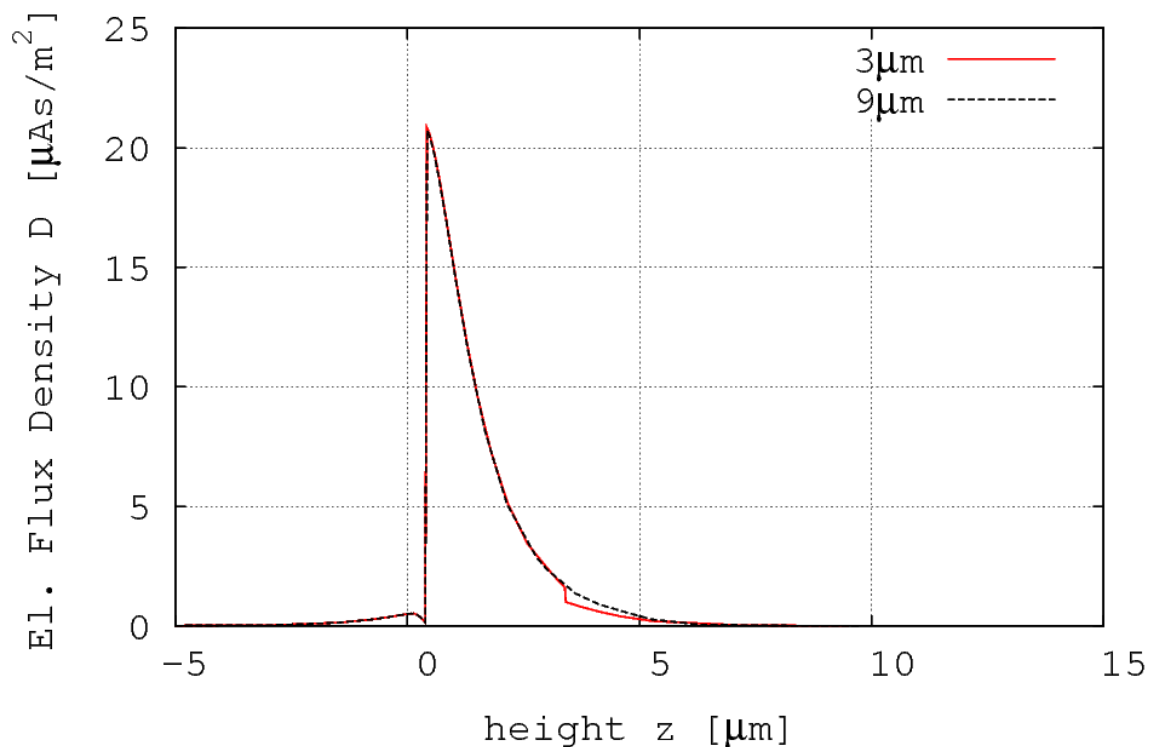
Comparison between experimental and numerical data.

Suppl. Figure 1



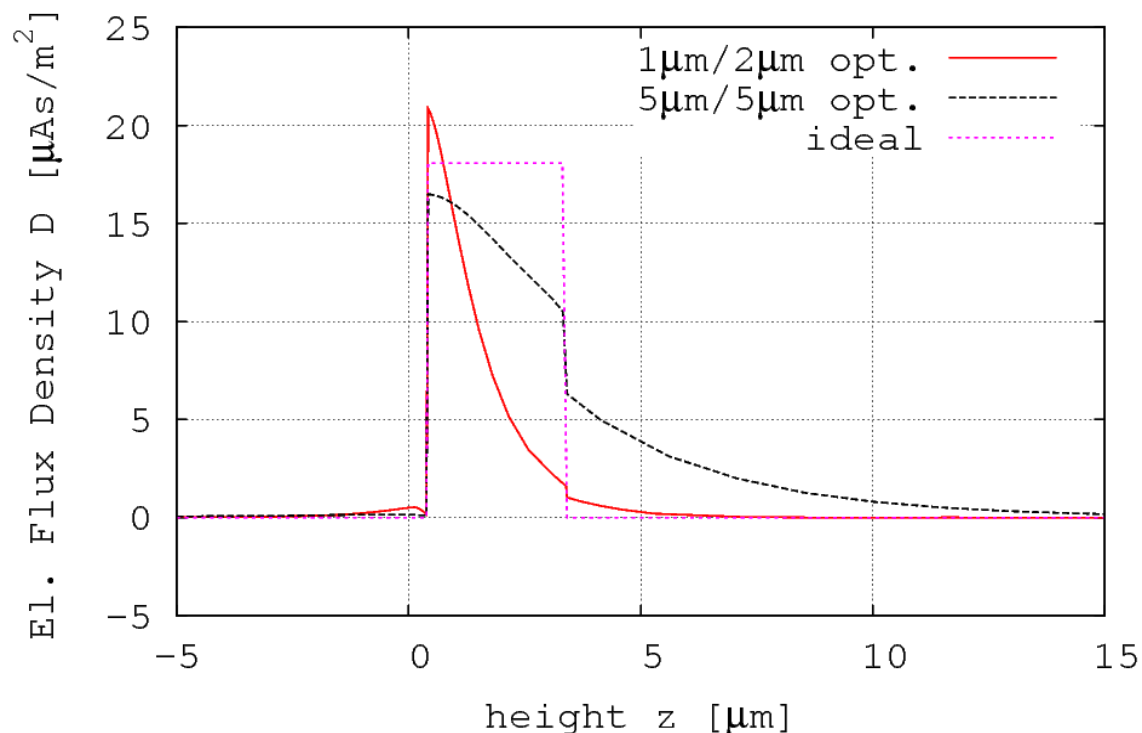
Dielectric flux density in x-direction  $D_x$  for a lab-on-a-chip with a homogeneous passivation layer, a finger width of  $1 \mu\text{m}$  and a finger distance of  $2 \mu\text{m}$  along a line which is parallel to the  $z$ -axis and placed in the center of the  $\mu\text{IDC}$  at an equal distance to the positive and the negative electrodes (inlet). The chamber of the chip is filled with distilled water.

Suppl. Figure 2



Dielectric flux density in x-direction  $D_x$  for a lab-on-a-chip with a finger width of  $1\mu\text{m}$  and a finger distance of  $2\mu\text{m}$  along a line which is parallel to the z-axis and placed in the center of the  $\mu\text{IDC}$  at an equal distance to the positive and the negative electrodes. Suppl Figure 2 illustrates  $D_x$  of a lab-on-a-chip with optimized passivation layer for a  $3\mu\text{m}$  and  $9\mu\text{m}$  high cell layer with a relative permittivity of 150.

Suppl. Figure 3



Suppl. Figure 3 compares the electric flux density in x-direction  $D_x$  for two different finger dimensions: a) finger width of 1  $\mu\text{m}$  and finger distance of 2  $\mu\text{m}$  and b) finger width of 5  $\mu\text{m}$  and finger distance of 5  $\mu\text{m}$ . The figure clearly shows that the maximum dielectric flux density is obtained for the  $\mu\text{IDC}$  with 1  $\mu\text{m}/2 \mu\text{m}$  structure. However, the dielectric flux  $D_x$  of the 1  $\mu\text{m}/2 \mu\text{m}$  sensor decreases more strongly with increasing distance from the electrodes than the dielectric flux  $D_x$  in the 5  $\mu\text{m}/5 \mu\text{m}$  finger structure. The three simulated curves show the distinctive step at the cell-water interface caused by the differing values of the permittivity in the cell and in the water region. Suppl. Figure 3 also illustrates the ideal electric flux density inside the lab-on-a-chip devices, which should be zero in all regions except in the cell layer (object to be measured), where a constant dielectric flux would be beneficial.